

COMPOSITE STRUCTURE AND ASSOCIATED PRODUCTION METHOD

FIELD OF THE INVENTION

5 The present invention relates to the field of composite structures and heterostructures. More specifically, it relates to composite structures for acoustic wave devices.

TECHNOLOGICAL BACKGROUND OF THE INVENTION

10 In the field of surface or bulk acoustic wave devices (hereinafter "SAW" and "BAW" respectively), heterostructures comprising a layer of lithium tantalate (LiTaO₃) arranged on a silicon substrate, are of increasing interest: on the one hand, because they are compatible with standard microelectronics equipment
15 and processes owing to their silicon support substrate and, on the other hand, because they have technical advantages such as, for example, a lower temperature

dependence of the frequency response of SAW devices, as explained in the article by K. Hashimoto, M. Kadota et al., "Recent development of temperature compensated SAW devices", IEEE Ultrason. Symp. 2011, pages 79 to 86, 2011.

LiTaO₃/Si heterostructures can, for example, be developed based on assembly through bonding by molecular adhesion of two substrates made of LiTaO₃ and Si, respectively. To manufacture acoustic wave devices on these heterostructures, it is advantageous to be able to reach a temperature of at least 250 °C to enable the use of materials and processes, guaranteeing that high-performing devices are achieved. The strength of the bonding interface between the LiTaO₃ layer and the Si support substrate is one of the essential factors in providing the structure with appropriate mechanical strength at high temperatures, in particular at temperatures greater than or equal to 250 °C.

This leads to the issue with increasing the heterostructure's bonding energy prior to any manufacturing steps of the acoustic wave device, at a temperature range around 250 °C, despite the significant difference in coefficient of thermal expansion (CTE) of the two materials.

Moreover, when a heterostructure with a very thin LiTaO₃ layer is required (e.g. to manufacture bulk acoustic wave devices, i.e. BAW devices), one solution is to transfer said layer using the Smart Cut® process,

including the formation of a fragile plane buried in a LiTaO₃ donor substrate by introducing light species such as hydrogen and/or helium, direct bonding of this donor substrate onto a silicon support substrate, and
5 separation at the buried fragile plane so as to transfer a LiTaO₃ surface layer onto Si. It is known that the surface layer still has defects and light species in its thickness after it has been transferred. Therefore, to heal this layer, it is advantageous to
10 anneal at a suitable temperature range to allow for the defects to be healed and the light species to be released without damaging the qualities of the thin layer transferred or the mechanical strength of the heterostructure. By way of example, the suitable
15 temperature range to choose for a LiTaO₃ layer would be between 400 °C and 600 °C.

Again, the issue is that LiTaO₃/Si heterostructures cannot handle these high thermal budgets, given the very significant difference in the
20 coefficient of thermal expansion between the materials LiTaO₃ and Si.

OBJECT OF THE INVENTION

One object of the invention therefore is to provide a structure and a manufacturing method
25 overcoming the drawbacks of the prior art. More specifically, one object of the invention is to provide a composite structure, comprising a useful layer arranged on a support at an interface and capable of

handling thermal budgets high enough to reinforce this interface or at least partially heal the defects on the surface layer or to develop certain components.

BRIEF DESCRIPTION OF THE INVENTION

5 The invention relates to a composite structure for an acoustic wave device comprising a heterostructure including:

 - a useful layer of piezoelectric material, having a first and a second face, the first face being
10 arranged at a first bonding interface on a support substrate having a lower coefficient of thermal expansion than that of the useful layer

 The composite structure is remarkable in that it comprises a functional layer an entire surface of which
15 is arranged at a second bonding interface on the second face of the useful layer and having a coefficient of thermal expansion less than that of the useful layer.

 The composite structure according to the invention thus is able to handle a temperature higher
20 than a limit temperature above which the heterostructure deteriorates or breaks in the absence of the functional layer. The composite structure thus makes it possible to apply heat treatments required to consolidate the first bonding interface of the
25 heterostructure or to heal any defects on the useful layer. It would not have been possible to apply these heat treatments directly to the heterostructure due to

the significant difference in coefficients of thermal expansion of the materials that the useful layer and the support substrate are made of.

According to advantageous characteristics of the invention, taken either separately or in combination:

- The functional layer has a thickness greater than or equal to 10 microns
- The useful layer consists of a material selected from among the following group: lithium tantalate (LiTaO_3), lithium niobate (LiNbO_3), aluminium nitride (AlN), zinc oxide (ZnO)
- The functional layer consists of a material selected from among the following group: silicon, III-V semiconductors, silicon carbide, glass, sapphire
- The support substrate consists of a material selected from among the following group: silicon, III-V semiconductors, silicon carbide, glass, sapphire
- The functional layer consists of the same material as that of the support substrate
- The adhesion energy of the first bonding interface between the useful layer and the support substrate of the heterostructure is greater than or equal to 1500 mJ/m²
- The adhesion energy of the second bonding interface between the functional layer and the

heterostructure is less than 1000 mJ/m², to enable its disassembly

• The functional layer comprises at least one first local opening enabling access to at least one first part of the second face of the useful layer and said first part of the second face of the useful layer comprises metal elements forming an acoustic wave device, in particular a SAW device

• The functional layer comprises at least one first local opening enabling access to at least one first part of the second face of the useful layer

• The support substrate comprises at least one second local opening, at least partially facing the first local opening and enabling access to at least one second part of the first face of the useful layer

• Said first and second parts respectively of the second and first faces of the useful layer comprise metal elements forming an acoustic wave device, in particular a BAW device

• The functional layer and/or the support substrate comprise(s) metal contacts and/or electronic devices electrically connected to metal elements arranged on the useful layer

The invention further relates to a method of manufacturing a composite structure for an acoustic wave device including a step of providing a

heterostructure comprising a useful layer of piezoelectric material having a first and a second face, the first face being arranged at a first bonding interface on a support substrate having a coefficient of thermal expansion less than that of the useful layer, the method is remarkable in that it includes the following:

- An assembly step forming a second bonding interface between an entire surface of a functional layer and the second face of the useful layer to form a composite structure, the functional layer having a coefficient of thermal expansion less than that of the useful layer

- A step in which a heat treatment is applied to the composite structure at a temperature higher than a limit temperature above which the heterostructure deteriorates or breaks in the absence of the functional layer

According to advantageous characteristics of the invention, taken either separately or in combination:

- The assembly step comprises a step for adjusting the thickness of the functional layer, performed prior to the heat treatment step, to achieve a functional layer thickness greater than or equal to 10 microns

- The temperature of the heat treatment step is greater than or equal to 250 °C, in particular between 250 °C and 600 °C

5 • The manufacturing method includes a step in which the functional layer is removed after the heat treatment step, through disassembly at the second bonding interface between the functional layer and the useful layer

10 • The disassembly is performed by applying a mechanical stress at the second bonding interface of the composite structure

15 • The manufacturing method includes a step of locally removing the functional layer to enable access to a first part of the second face of the useful layer, and a step of producing acoustic wave devices comprising metal elements on said first part

20 • The manufacturing method further includes a step of locally removing the support substrate to enable access to a second part of the first face of the useful layer, and a step of producing acoustic wave devices comprising metal elements on said second part

25 • The manufacturing method further includes a step of producing components on the functional layer and/or on the support substrate, and/or a step of electrical connection between metal elements arranged on the useful layer and metal contacts arranged on the functional layer and/or on the support substrate

BRIEF DESCRIPTION OF THE DRAWINGS

Further characteristics and advantages of the invention will be clear from the detailed description of the invention, made in reference to the appended figures, among which:

- Figures 1a to 1e show a heterostructure and a composite structure according to the invention

- Figures 2a to 2C show an alternative implementation of the composite structure

- Figure 3 shows another alternative implementation of the composite structure

- Figures 4a to 4c show steps of the manufacturing method according to the invention of the composite structure

DETAILED DESCRIPTION OF THE INVENTION

The invention relates to a composite structure 9 for acoustic wave devices comprising a heterostructure 5 (shown in Fig. 1c). The latter includes a useful layer 2 made of piezoelectric material, having a first face 3 and a second face 4, as shown in Fig. 1a. It also includes a support substrate 1 having a lower coefficient of thermal expansion than that of the useful layer 2. To form the heterostructure 5, the useful layer 2 is arranged along its first face 3 on the support substrate 1 (Fig. 1b). The useful layer 2

of the heterostructure 5 may consist of a material selected from among the following group: lithium tantalate (LiTaO_3), lithium niobate (LiNbO_3), aluminium nitride (AlN), zinc oxide (ZnO). The support substrate 1 of the heterostructure 5 may consist of a material selected from among the following group: silicon, III-V semiconductors, silicon carbide, glass, sapphire. The assembly of the useful layer 2 on the support substrate 1 is for example achieved through direct bonding by molecular adhesion. According to one variant, an additional layer (not shown), e.g. made of silicon oxide, may be deposited on the support substrate 1 and/or on the first face 3 of the useful layer prior to assembly. This configuration may, for example, facilitate bonding between the useful layer 2 and the support substrate 1.

There is a growing interest for a heterostructure 5 comprising a useful layer 2 made of piezoelectric material in the field of acoustic wave devices, which are among others used for mobile telephony applications and radiofrequency communications. Several steps are required to manufacture acoustic wave devices on a heterostructure 5, among which deposition of insulating and conductive layers, wet or dry etching, heat treatment (in the range of 150-250 °C). The applicant has observed that proper consolidation of the bonding interface between the useful layer 2 and the support substrate 1 favours the stability of the heterostructure 5 during device development steps, in

particular heat treatment steps. The object of the composite structure 9 according to the invention therefore is to make it possible to increase the bonding energy of the interface between the useful layer 2 and the support substrate 1 (called first bonding interface) of the heterostructure 5, in view of subsequent device development steps.

The composite structure 9 according to the invention thus comprises a functional layer 6, having two faces 7 and 8 (Fig. 1b). This layer 6 is assembled onto the second face 4 of the useful layer 2, so that the entire surface of one of its faces 7, 8 (in this case the face 7, in Fig. 1c) is arranged on the second face 4 of the useful layer 2 (at the level of a second bonding interface). The functional layer 6 also has a lower coefficient of thermal expansion than that of the useful layer 2. The functional layer 6 may consist of a material selected from among the following group: silicon, III-V semiconductors, silicon carbide, glass, sapphire. Advantageously, the functional layer 6 may consist of the same material as the support substrate 1. According to one variant, an intermediate layer (not shown) may be present between the functional layer 6 and the useful layer 2, for example made of silicon oxide, silicon nitride, etc. The intermediate layer may have been deposited on the second face 4 of the useful layer 2 and/or on the face 7 of the functional layer 6 prior to assembly.

The composite structure 9 according to the invention is compatible with a heat treatment temperature that is higher than a limit temperature above which the heterostructure 5 deteriorates or breaks in the absence of the functional layer 6. In fact, because of the large difference in the coefficient of thermal expansion (CTE) between the piezoelectric material forming the useful layer 2 and the material forming the support substrate 1, the heterostructure 5 will deteriorate (the support substrate 1 cracks or breaks, the useful layer 2 separates from its first face 3, the useful layer 2 is dislocated or deformed) if it is subjected to a temperature higher than a limit temperature. This limit temperature is related to the difference in CTE between the useful layer 2 and the support substrate 1 and to the respective thicknesses of the useful layer 2 and of the support substrate 1. By way of example, for a heterostructure consisting of a useful layer 2 made of LiTaO₃ 10 microns thick and a support substrate 1 made of Si 625 microns thick, the limit temperature is of the order of 150 °C. The composite structure 9 according to the invention allows for a temperature that is higher than this limit temperature to be applied. For example, the addition of a functional layer 6 made of Si 200 microns thick on the aforementioned example of a heterostructure 5 allows for a heat treatment in the range of 200-400 °C to be applied. A heat treatment in this temperature range is advantageous to consolidate the first bonding interface

between the useful layer 2 and the support substrate 1 of the heterostructure 5 and makes it possible to achieve higher bonding energies than with a treatment at a temperature below 150 °C.

5 A heterostructure 5 comprising a very thin useful layer 2 made of piezoelectric material may also be of interest in the field of acoustic wave devices, in particular BAW devices. One solution for producing such a heterostructure is to transfer said useful layer 2
10 using the Smart Cut® process, including the formation of a fragile plane buried in a donor substrate made of piezoelectric material by introducing light species such as hydrogen or helium, direct bonding of this donor substrate onto a support substrate 1 made of
15 silicon, and separation at the buried fragile plane so as to transfer a surface layer made of piezoelectric material onto Si. It is known that the surface layer still has defects and light species in its thickness after it has been transferred, which may among others
20 deteriorate its piezoelectric characteristics. To heal this layer, it therefore is essential to apply a heat treatment at an appropriate temperature range: to allow at least part of the defects to be healed and the light species to be released, but without damaging the
25 qualities of the thin layer transferred or the mechanical strength of the heterostructure 5. By way of example, suitable temperature range to choose for a LiTaO₃ layer would be between 400 °C and 600 °C, i.e. below the Curie temperature of the material.

Another object of the composite structure 9 according to the invention is to allow a healing annealing to be applied to the useful layer 2 of the heterostructure 5, in order to restore its piezoelectric characteristics. By way of example, for a heterostructure consisting of a useful layer 2 made of LiTaO₃ 0.5 micron thick and a support substrate 1 made of Si 625 microns thick, the limit temperature is of the order of 400 °C. The composite structure 9 according to the invention allows for a temperature higher than this limit temperature to be applied. For example, the addition of a functional layer 6 made of Si 50-100 microns thick on the aforementioned heterostructure 5 would allow a heat treatment in the range of 500-600 °C to be applied.

Advantageously, and accounting for the significant differences in CTE between the useful layer 2 and the support substrate 1 (and the functional layer 6), the functional layer 6 will have a thickness greater than or equal to 10 microns. Preferably, the functional layer 6 will even have a thickness greater than or equal to 50 microns.

According to a first variant of implementation of the composite structure 9 according to the invention, the functional layer 6 is removed after the heat treatment, intended to consolidate the first bonding interface of the heterostructure 5 and/or to heal all or part of the defects in the useful layer 2, is applied to the composite structure 9. The selected

adhesion energy of the second bonding interface between the functional layer 6 and the second face 4 of the useful layer 2 of the heterostructure 5 will be less than 1000 mJ/m², to allow for disassembly of the functional layer 6. The term disassembly is used here to convey the separation between the functional layer 6 and the heterostructure 5 at the second bonding interface.

The present invention thus makes it possible to obtain a heterostructure 5 whose mechanical strength (consolidated bonding interface) and electrical characteristics (defects of the useful layer fully or partially healed) are compatible with the subsequent development of acoustic wave devices on the useful layer 2. In particular, the adhesion energy between the useful layer 2 and the support substrate 1 of the heterostructure 5 is greater than or equal to 1500 mJ/m².

According to a second implementation variant of the composite structure 9 according to the invention, and as shown in Fig. 2a, one or more first local opening(s) 10 is (are) arranged in the functional layer 6 of the composite structure 9, enabling access to at least one first part 11 of the second face 4 of the useful layer 2. Components can thus be developed on the useful layer 2, at the level of the at least one first part 11. The first part 11 of the second face 4 of the useful layer comprises among others metal elements 12 forming an acoustic wave device, in particular a SAW

device (Fig. 2b). The metal elements 12 may for example consist of interdigitated electrodes and associated contact pads.

5 The composite structure 9 according to this second variant may provide a more advantageous mechanical strength than the heterostructure 5 alone. More specifically, it may be compatible with heat treatments at higher temperatures than a heterostructure 9 devoid of any functional layer 6,
10 when manufacturing the acoustic wave device.

 According to an optional mode of implementation of this second variant, the functional layer 6 comprises metal contacts 13 and/or electronic devices 14 electrically connected to certain metal elements 12
15 arranged on the useful layer 2. In this mode of implementation, the composite structure 9 enables the contact pads of the SAW devices on the useful layer 2 to be displaced to the face 8 of the functional layer 6. This configuration may be of interest especially to
20 facilitate vertical interconnections and an assembly with a cover 15 ("wafer level packaging", shown in Fig. 2c). The composite structure 9 furthermore makes it possible to co-integrate components, some 12 developed on a piezoelectric material (the useful layer 2),
25 others 14 developed on the functional layer 6 (e.g. a silicon-type semi-conductor layer).

 According to a third variant of implementation of the composite structure 9 according to the invention,

and as shown in Fig. 3, the support substrate 1 also comprises one (or several) second local opening(s) 16 enabling access to the at least one second part 17 of the first face 3 of the useful layer 2. The second
5 local opening 16 will be at least partially facing a first local opening 10 arranged in the functional layer 6; the first local opening 10 enables access to at least one first part 11 of the second face 4 of the useful layer 2. The first 11 and second 17 parts
10 respectively of the second 4 and first 3 faces of the useful layer 2 comprise metal elements forming an acoustic wave device, e.g. a BAW device. The functional layer 6 and/or the support substrate 1 comprise(s) metal contacts 13, 20 and/or electronic devices 14
15 electrically connected to certain metal elements 12, 18 arranged on the first 11 and second 17 parts of the useful layer. 2. As shown in Fig. 3, metal elements 18 arranged on the second part 17 of the useful layer 2 may be connected to contact pads 20 on the functional
20 layer 6 by means of through-hole vias 19.

The invention also relates to a method for manufacturing a composite structure 9 for an acoustic wave device. The method includes a step of providing a heterostructure 5 comprising a useful layer 2 of
25 piezoelectric material, having a first face 3 and a second face 4 (Fig. 4a). The first face 3 is arranged on a support substrate 1 having a lower coefficient of thermal expansion than that of the useful layer 2. The method further comprises a step of assembling the

entire surface of a face 7 of a functional layer 6 (Fig. 4a) on the second face 4 of the useful layer 2 to form the composite structure 9 (Fig. 4b), the functional layer 6 having a lower coefficient of thermal expansion than that of the useful layer 2. This assembly step may consist in direct bonding by molecular adhesion. The surfaces to be assembled, respectively of the functional layer 6 and of the useful layer 2, may advantageously undergo a cleaning sequence to prepare them for direct bonding. For example, chemical cleaning based on ozone and RCA may be applied as well as an O₂ or N₂ plasma treatment for surface activation. Optionally, an intermediate layer may be deposited on the face 7 of the functional layer 6 and/or on the face 4 of the useful layer 2, e.g. a silicon oxide or silicon nitride layer.

The method according to the invention also comprises a step in which a heat treatment is applied to the composite structure 9 at a temperature higher than a limit temperature above which the heterostructure 5 deteriorates or breaks in the absence of the functional layer 6. In fact, because of the large difference in the coefficient of thermal expansion (CTE) between the piezoelectric material forming the useful layer 2 and the material forming the support substrate 1, the heterostructure 5 will deteriorate (the support substrate 1 cracks or breaks, the useful layer 2 separates from its first face 3, the useful layer 2 is dislocated or deformed) when it is

subjected to a temperature higher than a limit temperature. This limit temperature is related to the difference in CTE between the useful layer 2 and the support substrate 1 and to the respective thicknesses
5 of the useful layer 2 and of the support substrate 1.

It is essential that the entire surface of the face 7 of the functional layer 6 is assembled onto the second face 4 of the useful layer 2, so as to uniformly control the differential expansion between the
10 functional layer 6 and the useful layer 2 and to provide the composite structure with the best mechanical strength during subsequent heat treatment. Local bonding of the functional layer 6 to the useful layer 2 would be less favourable for the mechanical
15 strength of the composite structure 9 at temperatures higher than the limit temperature supported by the heterostructure 5. During the heat treatment step, the composite structure 9 will thus be compatible with a temperature greater than or equal to 250 °C, more
20 specifically between 250 °C and 600 °C, depending on the materials and the respective thicknesses of the functional 6 and useful 2 layers and of the support substrate 1.

According to one variant, the method according to
25 the invention comprises a step for adjusting the thickness of the functional layer 6 (Fig. 4c), performed prior to the heat treatment step, to achieve a functional layer 6 thickness that is greater than or equal to a threshold thickness. Advantageously, this

threshold thickness will be chosen to be greater than or equal to 10 microns. Preferably, the functional layer 6 will even have a thickness greater than or equal to 50 microns.

5 The thickness adjustment step may consist in mechanical, chemical-mechanical and/or chemical thinning.

 According to a first implementation variant, the method according to the invention may comprise a step
10 in which the functional layer 6 is removed, after the heat treatment step, through disassembly of the composite structure 9 at a bonding interface, between the functional layer 6 and the useful layer 2 (called the second bonding interface). The assembly step of the
15 method between the functional layer 6 and the useful layer 2 must have been performed in such a way that the second bonding interface can later be disassembled. More specifically, it must have been performed in such a way that the bonding energy at this interface is less
20 than 1000 mJ/m². By way of example, the assembly step may consist in oxide/oxide bonding, the face 7 of the functional layer 6 and the face 4 of the useful layer 2 being provided with a silicon oxide layer. The surface roughness of the oxide layers must be chosen in the
25 range of 0.1 to 0.5 nm RMS, so as to obtain a bonding energy of less than 1000 mJ/m², e.g. of the order of 500 mJ/m².

Disassembly, after the heat treatment step, may for example be performed by applying a mechanical stress at the second bonding interface of the composite structure 9, i.e. at the interface between the functional layer 9 and the useful layer 2.

Following this step of removing the functional layer 9, the heterostructure 5 is obtained with a consolidated bonding interface that is compatible with the subsequent steps of manufacturing an acoustic wave device.

Alternatively, the complete removal of the functional layer 6 can be achieved by mechanical, chemical-mechanical or chemical thinning techniques.

According to a second variant of implementation, the method according to the invention comprises a step of local removal of the functional layer 6 to enable access to at least one first part 11 of the second face 4 of the useful layer 2. This local removal step may consist in wet or dry chemical etching in areas defined, for example, using photolithography techniques. By way of example, local removal may be achieved on a plurality of areas enabling access to a percentage (opening rate) of the second face 4 of the useful layer 2. The opening rate ranges from a few % to < 100%, depending on the devices to be developed. The method then comprises a step of producing acoustic wave devices comprising metal elements 12 on the plurality of first parts 11 (Fig. 2b). This step of producing

devices may include among others the development of contact pads 13 on the functional layer 6, which are electrically connected to the acoustic wave devices on the useful layer 2.

5 According to a third implementation variant, which may or may not be combined with the second mode of implementation, the method according to the invention may further comprise a step of locally removing the support substrate 1 to enable access to at
10 least one second part 17 of the first face 3 of the useful layer 2. This local removal step may consist in wet or dry chemical etching in areas defined, for example, using photolithography techniques.

 By way of example, local removal may be achieved
15 in a plurality of areas with an opening rate ranging from 1% to 50%. Advantageously, to enable the production of bulk acoustic wave devices, the plurality of second parts 17 and the plurality of first parts 11 will be facing each other at least partially, thus
20 making it possible to obtain a local self-bearing useful layer 2 membrane. The method then includes a step of producing acoustic wave devices comprising metal elements 18 on the plurality of second parts 17 of the useful layer 2, as shown in Fig. 3.

25 Optionally, the method may include a step of producing components 14 on the functional layer 6 and/or on the support substrate 1, and/or a step of electrical connection between metal elements 12, 18

arranged on the useful layer 2 and metal contacts 13, 20 arranged on the functional layer 6 and/or on the support substrate 1.

Example 1:

5 A heterostructure 5 comprising a useful layer 2 made of lithium niobate (LiNbO_3) 20 microns thick and a support substrate 1 made of silicon (Si) 625 microns thick and 150 mm in diameter has a bonding energy well below 1 J/m². Prior to producing the acoustic wave
10 devices on this heterostructure, it is essential to strengthen its bonding interface. To achieve this, a heat treatment must be applied to it at a temperature of 250 °C for 2 h.

 The functional layer 6 is a silicon substrate
15 (150 mm in diameter and 625 microns thick) comprising an intermediate layer of silicon oxide 400 nm thick on its front face 7. The silicon oxide layer has a surface roughness of the order of 0.2 nm RMS. The functional layer 6 then undergoes cleaning (typically ozone and
20 RCA), prior to its assembly onto the second face 4 of the useful layer 2 of the heterostructure 5. The heat treatment at 250 °C is then applied to the composite structure 9 for 2 h. The composite structure is able to withstand a thermal budget of 250 °C/2 h, without being
25 damaged and without generating any deterioration of the heterostructure 5. If used alone, the heterostructure 5 would have deteriorated (cracking or breakage of the support substrate 1 and/or partial or complete

separation of the useful layer 2), had it been subjected to this thermal budget prior to reinforcing its bonding interface, or even at a lower thermal budget of the order of 200 °C.

5 Once the heat treatment has been performed, the functional layer 6 is disassembled by inserting a bevelled tool at the level of the bonding interface between the functional layer 6 and the useful layer 2. The heterostructure 5 has a reinforced bonding
10 interface, of the order of 1.5 J/m², which provides suitable mechanical strength during the subsequent acoustic wave device development steps.

Example 2:

15 A heterostructure 9 is formed out of a useful layer 2 made of lithium tantalate (LiTaO₃) 0.3 microns thick and a support substrate 1 made of silicon (Si) 625 microns thick and 150 mm in diameter. The useful layer 2 was transferred using the Smart Cut® process and, after separation, had defects in its thickness
20 that are prohibitive for producing acoustic wave devices, since they affect the piezoelectric properties of the useful layer 2. Prior to producing the acoustic wave devices on this heterostructure 5, it is therefore essential to heal all or part of these defects. To
25 achieve this, a heat treatment must be applied at a temperature of 550 °C for 2 h.

The functional layer 6 is a silicon substrate (150 mm in diameter and 625 microns thick) comprising an intermediate layer made of silicon oxide 400 nm thick on its front face 7. It undergoes cleaning (typically ozone and RCA) and an O₂ plasma treatment, prior to being assembled onto the second face 4 of the useful layer 2 of the heterostructure 5. A thickness adjustment step is then carried out on the functional layer 6 using mechanical thinning (grinding) and then chemical-mechanical polishing to achieve a final thickness of 200 microns.

The composite structure 9 thus formed is able to withstand a thermal budget of 550°C/2 h, without being damaged and without generating any deterioration of the heterostructure 5. If used alone, the heterostructure 5 would have deteriorated (cracking or breakage of the support substrate 1 and/or partial or complete separation of the useful layer 2), had it been subjected to this thermal budget without any functional layer 6.

The heat treatment having been applied to the composite structure 9, the functional layer 6 is disassembled by applying a localized stress to the second bonding interface between the functional layer 6 and the useful layer 2. Alternatively, the functional layer 6 is removed by a mechanical followed by a chemical thinning sequence.

The heterostructure 5 has a reinforced bonding interface, greater than or equal to 1.5 J/m² due to the thermal budget applied and the useful layer 2 has been healed of the majority of the defects related to the implantation of light species such as hydrogen or helium (Smart Cut® process), making it compatible with the production of acoustic wave devices. By way of example, the extent to which the defects in the useful layer 2 have been healed can be assessed by producing electrical devices and testing their level of performance, making it possible to validate the electrical quality of said useful layer 2.

Example 3:

A heterostructure 9 is formed out of a useful layer 2 made of lithium tantalate (LiTaO₃) 0.3 microns thick and a support substrate 1 made of silicon (Si) 625 microns thick and 150 mm in diameter. The useful layer 2 was transferred using the Smart Cut® process and, after separation, had defects in its thickness that are prohibitive for producing acoustic wave devices, since they affect the piezoelectric properties of the useful layer 2. Prior to producing the acoustic wave devices on this heterostructure 5, it is therefore essential to heal these defects. To achieve this, a heat treatment must be applied at a temperature of 500 °C for 2 h.

The functional layer 6 is a silicon substrate (150 mm in diameter and 625 microns thick) comprising

an intermediate layer made of silicon oxide 400 nm thick on its front face 7. It undergoes cleaning (typically ozone and RCA) and an O₂ plasma treatment, prior to being assembled onto the second face 4 of the useful layer 2 of the heterostructure 9. A thickness adjustment step is then carried out on the functional layer 6 using mechanical thinning (grinding) and then chemical-mechanical polishing to achieve a final thickness of 10 microns.

The composite structure 9 thus formed is able to withstand a thermal budget of 500°C/2 h, without being damaged and without generating any deterioration of the heterostructure 5. If used alone, the heterostructure 5 would have deteriorated (cracking or breakage of the support substrate 1 and/or partial or complete separation of the useful layer 2), had it been subjected to this thermal budget without any functional layer 6.

Since the heat treatment has been applied to the composite structure 9, the heterostructure 5 has a reinforced bonding interface, greater than 1.5 J/m² due to the thermal budget applied and the useful layer 2 has been healed of a large part of the defects related to the implantation of light species such as hydrogen or helium (Smart Cut® process), making it compatible with the production of acoustic wave devices.

A step consisting in local removal of the functional layer 6 is then carried out to enable access

to at least one first part 11 of the second face 4 of the useful layer 2. This local removal step may consist in wet or dry chemical etching at the level of areas defined using photolithography. The local removal can
5 be performed in a plurality of areas enabling access to a plurality of first parts 11 and representing an opening rate of the order of 50%. Acoustic wave devices can then be developed on the plurality of first parts 11 of the useful layer 2. These devices comprise metal
10 elements 12, typically interdigitated electrodes. The presence of the functional layer 6 on the useful layer 2, even if partial, makes it possible to carry out treatments at higher temperatures than in the case where the heterostructure 5 is used alone. This is
15 favourable for the use of more efficient materials or technologies to produce acoustic wave devices.

Contact pads 13 on the functional layer 6 may be electrically connected to the acoustic wave devices on the useful layer 2. Components can also be developed on
20 the functional layer 6. The composite structure 9 thus facilitates the co-integration of components on piezoelectric materials (the useful layer) and on semiconductor materials (the functional layer).

Of course, the invention is not limited to the
25 sole modes of implementation described and various implementations can be provided without going beyond the ambit of the invention as defined by the claims.

The composite structure according to the invention is of great interest for the manufacturing of acoustic wave devices, for example in the field of SAW and BAW filters for radiofrequency applications, but
5 also in the field of piezoelectric sensors. In fact, since the latter enable the transformation of mechanical movements into electrical signals, and this with a very high sensitivity, several fields of application open or are likely to open in the areas of
10 temperature sensors, energy harvesting, etc.

CLAIMS

1. A composite structure (9) for an acoustic wave device comprising a heterostructure (5) including:

5 a useful layer (2) of piezoelectric material, having a first (3) and a second (4) face, the first face (3) being arranged at a first bonding interface on a support substrate (1) having a lower coefficient of thermal expansion than that of the useful layer (2),

10 the composite structure (9) being characterized in that it comprises a functional layer (2) an entire surface of which is arranged at a second bonding interface on the second face (4) of the useful layer (2) and having a lower coefficient of thermal expansion than that of the useful layer (2).

15 2. The composite structure (9) for acoustic wave device of the preceding claim, wherein the functional layer (6) has a thickness greater than or equal to 10 microns.

20 3. The composite structure (9) for acoustic wave device of one of the preceding claims, wherein the useful layer (2) consists of a material selected from among the following group: lithium tantalate (LiTaO₃), lithium niobate (LiNbO₃), aluminium nitride (AlN), zinc oxide (ZnO).

25 4. The composite structure (9) for acoustic wave device of one of the preceding claims, wherein the

functional layer (6) consists of a material selected from among the following group: silicon, III-V semiconductors, silicon carbide, glass, sapphire.

5 5. The composite structure (9) for acoustic wave device of one of the preceding claims, wherein the support substrate (1) consists of a material selected from among the following group: silicon, III-V semiconductors, silicon carbide, glass, sapphire.

10 6. The composite structure (9) for acoustic wave device of one of the preceding claims, wherein the functional layer (6) consists of the same material as that of the support substrate (1).

15 7. The composite structure (9) for acoustic wave device of one of the preceding claims, wherein the adhesion energy of the first bonding interface between the useful layer (2) and the support substrate (1) of the heterostructure (5) is greater than or equal to 1500 mJ/m².

20 8. The composite structure (9) for acoustic wave device of one of the preceding claims, wherein the adhesion energy of the second bonding interface between the functional layer (6) and the heterostructure (5) is less than 1000 mJ/m² to enable its disassembly.

25 9. The composite structure (9) for acoustic wave device of one of claims 1 to 7, wherein the functional layer (6) comprises at least one first local opening (10) enabling access to at least one first part (11) of

the second face (4) of the useful layer (2) and wherein said first part (11) of the second face (4) of the useful layer (2) comprises metal elements (12) forming an acoustic wave device, in particular a SAW device.

5 10. The composite structure (9) for acoustic wave device of one of claims 1 to 7, wherein:

 • the functional layer (2) comprises at least one first local opening (10) enabling access to at least one first part (11) of the second face (4) of the
10 useful layer (2),

 • the support substrate (1) comprises at least one second local opening (16), at least partially facing the first local opening (10) and enabling access to at least one second part (17) of the first face (3)
15 of the useful layer (2),

 • said first (11) and second (17) parts respectively of the second (4) and first (3) faces of the useful layer (2) comprise metal elements (12, 18) forming an acoustic wave device, in particular a BAW
20 device.

 11. The composite structure (9) for acoustic wave device of one of the two preceding claims, wherein the functional layer (6) and/or the support substrate (1) comprise(s) metal contacts (13) and/or electronic
25 devices (14) electrically connected to metal elements (12, 18) arranged on the useful layer.

12. A method of manufacturing a composite structure (9) for acoustic wave devices including a step of providing a heterostructure (5) comprising a useful layer (2) made of piezoelectric material having a first (3) and a second (4) face, the first face (3) being arranged at a first bonding interface on a support substrate (1) having a lower coefficient of thermal expansion than that of the useful layer (2), the method being characterized in that it includes:

- An assembly step forming a second bonding interface between an entire surface of a functional layer (6) and the second face (4) of the useful layer (2) to form a composite structure (9), the functional layer (6) having a lower coefficient of thermal expansion than that of the useful layer (2)

- A step in which a heat treatment is applied to the composite structure (9) at a temperature higher than a limit temperature above which the heterostructure (5) deteriorates or breaks in the absence of the functional layer (6)

13. The method of manufacturing a composite structure (9) for acoustic wave devices of the preceding claim, wherein the assembly step comprises a step for adjusting the thickness of the functional layer (6), performed prior to the heat treatment step, to achieve a functional layer (6) thickness greater than or equal to 10 microns.

14. The method of manufacturing a composite structure (9) for acoustic wave devices of the preceding claim, wherein the temperature of the heat treatment step is greater than or equal to 250 °C, and
5 more specifically contained between 250 °C and 600 °C.

15. The method of manufacturing a composite structure (9) for acoustic wave devices of one of the three preceding claims, comprising a step in which the functional layer (6) is removed after the heat
10 treatment step, through disassembly at the level of the second bonding interface between the functional layer (9) and the useful layer (2).

16. The method of manufacturing a composite structure (9) for acoustic wave devices of the
15 preceding claim, wherein the disassembly is performed by applying a mechanical stress at the second bonding interface of the composite structure (9).

17. The method of manufacturing a composite structure (9) for acoustic wave devices of one of
20 claims 12 to 14, comprising a step of locally removing the functional layer (9) to enable access to a first part (11) of the second face (4) of the useful layer (2), and a step of producing acoustic wave devices comprising metal elements (12) on said first part (11).

25 18. The method of manufacturing a composite structure (9) for acoustic wave devices of the preceding claim, further comprising a step of locally

removing the support substrate (1) to enable access to a second part (17) of the first face (3) of the useful layer (2), and a step of producing acoustic wave devices comprising metal elements (18) on said second
5 part (17).

19. The method of manufacturing a composite structure (9) for acoustic wave devices of one of the two preceding claims, further comprising a step of producing components (14) on the functional layer (6)
10 and/or on the support substrate (1), and/or a step of electrical connection between metal elements (12, 18) arranged on the useful layer (2) and metal contacts (13, 20) arranged on the functional layer (6) and/or on the support substrate (1).